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| Form PTO-1449 U.S. DEPARTMENT OF COMMERCE (REV. 8-83) PATENT AND TRADEMARK OFFICE | | | | ATTY. DOCKET NO. BU9-98-179 US2 | | SERIAL NO. | |
| INFORMATION DISCLOSURE CITATION (Use several sheets if necessary) | | | | APPLICANT Furukawa et al. | | | |
| | | | | FILING DATE | | GROUP | |
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| EXAMINER Qua Hoang | | | | DATE CONSIDERED 7/2004 | | | |
| *EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | | |

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